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FILM-FORMING COMPOSITION, METHOD FOR PRODUCING THE COMPOSITION, METHOD
FOR
FORMING POROUS FILM, AND THE POROUS FILM

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ABSTRACT

PROBLEM TO BE SOLVED: To provide a film-forming composition capable of forming a film that is porous, flat and uniform, and further has a low dielectric constant and a high mechanical strength, and therefore is most suitable as an insulating interlayer film when it is used in producing a semiconductor device, by using the composition.

SOLUTION: This silicone-containing film-forming composition contains (A) a

silanol group-containing silicone resin having a number-average molecular weight of ≥ 100 and (B) a polymer which is formed by polymerizing monomer(s) comprising acrylic ester(s), methacrylic ester(s) or a mixture thereof, wherein the silanol group-containing silicone resin contains a structural unit (T unit) expressed by the general formula (1): R_1-SiZ_3 (R_1 is a monovalent hydrocarbon radical which may be substituted or unsubstituted; and Z is OH, a hydrolyzable group or a siloxane residue, provided that at least one of Z s is a siloxane residue) in an amount of 30-100 mol%, and 30-80 mol% of the T units each comprise a structural unit (T-2 unit) which has a silanol group and is expressed by the general formula (2): $R_1-Si(OH)Z'_2$ (Z' is a siloxane residue).

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